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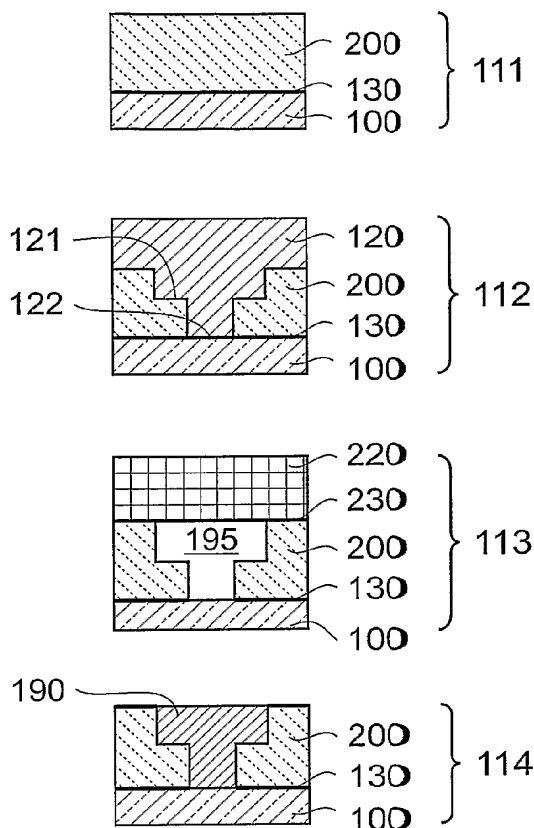
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(54) Title: FABRICATION METHOD



(57) Abstract: Described is a method for forming a multilevel structure on a surface. The method comprises: depositing a curable liquid layer (200) on the surface; pressing a stamp (120) having a multilevel pattern therein into the liquid layer to produce in the liquid layer a multilevel structure defined by the pattern; and, curing the liquid layer to produce a solid layer having the multilevel structure therein. Mechanical alignment may be employed to enhance optical alignment of the stamp relative to the substrate via a plurality of spaced protrusions on the substrate on which the structure is to be formed and complementary recesses in the patterning of the stamp.



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